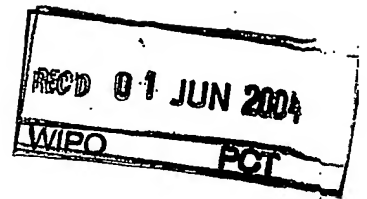


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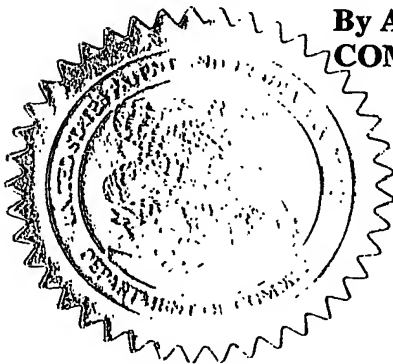
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☐ Additional inventors are being named on separately numbered sheets attached hereto**

TITLE OF THE INVENTION (280 characters max)

IMPROVED COMPOSITION AND METHOD FOR REMOVAL OF CARBONYL SULFIDE FROM ACID GAS CONTAINING SAME

CORRESPONDENCE ADDRESS

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ENCLOSED APPLICATION PARTS (check all that apply)

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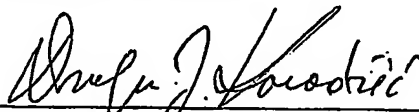
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The invention was made by an agency of the United States Government or under a contract with an agency of the United States Government

☒ No

☐ Yes, the name of the U.S. Government agency and the Government contract number are:

Respectfully submitted,



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PROVISIONAL APPLICATION FILING ONLY

IMPROVED COMPOSITION AND METHOD FOR REMOVAL OF CARBONYL SULFIDE FROM ACID GAS CONTAINING SAME

Background of the Invention

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The present invention relates to an improved composition for selective removal of carbonyl sulfide (COS) with minimal absorption of carbon dioxide (CO₂) from an acid gas containing COS and CO₂, and also to a method for selective removal of COS from an acid gas containing COS and CO₂ using this improved composition.

10

Natural and synthesis gas streams, derived from natural gas reservoirs, petroleum or coal, often contain a significant amount of carbonyl sulfide (COS) in addition to other impurities such as carbon dioxide (CO₂), hydrogen sulfide (H₂S), sulfur dioxide (SO₂), carbon disulfide (CS₂), mercaptans, and the like. Various compositions and processes for removal of acid gases, including COS, from a gas containing same are known and described in the literature.

Certain physical solvents have been widely used for the selective removal of H₂S from gas streams containing H₂S, CO₂ and optionally, other components. For example, dialkyl ethers of polyalkylene glycols are commonly specified for this purpose. Typical of the numerous disclosures of such solvents in the art is European Patent Application No. EP 0770420 A2 and U.S. Patent Nos. 3,737,392; 3,824,766; 3,837,143; 4,044,100; 4,336,233; 4,581,154; 4,741,745; and 4,946,620, among others. According to such references, it is well known that the solubility of H₂S in these glycols is much higher than the solubility of CO₂. This difference in solubility forms the basis for the selective removal of H₂S by glycol ethers and other physical solvents. Unfortunately, the solubility of COS in most physical solvents is not very different from the solubility of CO₂. Hence, selective removal of COS or COS and H₂S from gas streams containing CO₂ and optionally other components, has proved difficult.

30

Certain tertiary alkanolamines (methyldiethanolamine and triethanolamine for example) have been widely used for the selective removal of H₂S from gas streams which

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also contain CO₂. Users of these amines exploit the rapid reaction with H₂S and the slow reaction with CO₂ to allow selective removal of H₂S. Unfortunately, the reaction of these amines with COS is about 100 times slower than the reaction with CO₂. Hence, tertiary amines are relatively ineffective at separating COS or COS and H₂S from CO₂ containing streams.

Certain primary and secondary amines (monoethanolamine, diethanolamine, methylethanolamine, aminoethoxy ethanol, piperazine for example) have been widely used for the simultaneous removal of H₂S and CO₂. These amines react rapidly with both H₂S and CO₂ and are well suited for simultaneous removal of H₂S and CO₂. Although the reaction of COS with these amines is also about 100 times slower than the reaction with CO₂, appreciable amounts of CO₂ and COS can be removed. Unfortunately, since COS reacts much more slowly with these amines than does CO₂, selective removal of COS or COS and H₂S with primary or secondary amines has proved difficult.

The selective removal of COS or COS and H₂S from gas streams containing CO₂ and optionally other components has proved difficult with both physical and chemical solvents. However, in a number of conventional hydrocarbon processing techniques, it is desirable or necessary to remove COS down to few parts per million (ppmv) for several reasons, such as catalyst sensitivity to COS in subsequent operations and statutory or contract requirements regarding sulfur content in product or waste gas streams. The presence of COS has also been identified as the cause of degradation reactions in several commercial processes for acid gas removal. However, in many cases it is neither necessary nor desirable to remove CO₂ from gaseous mixtures.

Various solvent compositions and methods are known for selective removal of COS and H₂S from gaseous mixtures containing same and other acidic gases such as CO₂.

U.S. Patent No. 3,989,811 (Hill) discloses a multi-step process for removal of acid gases, that is, H₂S, CO₂, and sulfur containing compounds including CS₂, COS, and various mercaptans from sour gases. In this multi-step process, H₂S, CO₂ and COS are absorbed in a nonselective alkanolamine. The regenerated acid gases are then contacted with a selective

amine to produce an H₂S rich stripper off gas and a low pressure CO₂ rich stream. Suitable alkanolamines include methyldiethanolamine, triethanolamine, or one or more di-propanolamines, such as di-n-propanolamine or diisopropanolamine. The preferred absorbent for treatment of COS containing gas streams also contains a significant amount of a tetramethylene sulfone (the unsubstituted compound is known as sulfolane). In principle, selective removal of COS and H₂S from the original sour gas stream could be achieved if the CO₂ rich product stream were recompressed and combined with the main treated gas stream. However, the capital and operating costs associated with requiring two absorbers, two strippers and compression of the CO₂ stream would weigh against this option, assuming a less costly alternative can be found.

U.S. Patent No. 4,482,529 (Chen et al.) discloses a single step process for the selective removal of COS from a gas stream containing CO₂. Small amounts of bicyclo tertiary amine are added to a physical solvent already known to be selective for H₂S in the presence of CO₂. According to the invention, addition of the bicyclo tertiary amine encourages hydrolysis of the COS to H₂S and CO₂. The net effect is to improve the absorption of COS without substantially increasing the absorption of CO₂. Applicable physical solvents include SELEXOLTM solvent (a blend of polyethylene glycol dimethyl ethers sold by Union Carbide Corporation under the trademark SELEXOL), sulfolane, methanol and others.

U.S. Patent No. 4,524,050 (Chen et al.) discloses a process for hydrolyzing COS in gas streams to H₂S and CO₂ using solid supported bicyclo tertiary amine catalyst.

U.S. Patent No. 4,504,449 (Doerges et al.) discloses a process for selective removal of H₂S and possibly COS from a CO₂ containing gas stream using highly volatile secondary amines in an organic solvent. A complex regeneration scheme is required. Applicable secondary amines are diethyl amine, diisopropyl amine, methyl isopropyl amine, ethyl isopropyl amine, dipropyl amine, methyl n-butylamine, methyl isobutyl amine and methyl sec-butyl amine. Applicable organic solvents include alkylated polyethylene glycol ethers, tetrahydrothiophene dioxide etc.

U.S. Patent No. 4,532,116 (Doerges et al.) discloses a process for the removal of H_2S and/or COS from synthesis gas using at least one secondary amine and an organic solvent. Although the process is selective for H_2S and COS in the presence of CO_2 , the process is complex. Two scrubbing zones are required – a preliminary desulfurizing zone using a conventional circulated and regenerated solution and a fine desulfurizing or scrubbing zone using unregenerated solvent. The fine desulfurizing zone contains a heat exchanger to condense the unregenerated solvent. Applicable organic solvents are methanol, ethanol and isopropanol. Applicable secondary amines are N-ethylethaneamine, N-(1-methylethyl)propaneamine, N-methyl-2-propanamine, N-ethyl-2-propanamine, N-propyl-1-propanamine, N-methyl-1-butanamine, N-2-dimethyl-1-propanamine, N-methyl-2-butanamine.

U.S. Patent No. 4,749,555 (Bush) discloses a process for selective removal of H_2S and COS without absorbing CO_2 from a gas stream having a relatively large concentration of CO_2 using bridgehead amines (bicyclotertiary amine or bicyclo amidine), tertiary amine, physical solvent and water. Applicable physical solvents include sulfolane, polyethylene glycol dimethyl ethers and others.

U.S. Patent No. 4,980,140 (Souby) discloses a process for selective removal of COS from H_2S using a solvent comprising a tertiary amine, a physical co-solvent and a minor amount of water. The useful physical co-solvent includes sulfones, sulfoxides, glycols and the mono and diethers thereof, 1,3-dioxo heterocyclic compounds (dioxane and dioxolane), aromatic ethers, aromatic hydrocarbons and N-alkylated lactams of gamma or omega amino acids.

U.S. Patent No. 5,413,627 (Landeck et al.) discloses the selective removal of H_2S and COS from CO_2 using a physical scrubbing agent comprising a heterocycle having five or more ring atoms, which contains two heteroatoms, one of which is nitrogen and the other of which is oxygen or nitrogen. The nitrogen atom present in the ring is/are either double bonded or single bonded but, if single bonded, the nitrogen is organo-substituted. A wide variety of scrubbing agents are disclosed, including 1,3-dimethyl-3,4,5,6-tetrahydro-2(1H)-pyrimidinone (DMTP).

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U.S. Patent No. 5,589,149 (Garland et al.) discloses absorption solvents for removing mercaptans from gas streams without the use of iodine. The solvent comprises alkyl ether of a polyalkylene glycol and a secondary monoalkanolamine and, optionally,
5 other amines, such as dialkanolamines.

U.S. Patent No. 6,277,345 B1 (Stankowiak et al.) discloses the use of absorption liquid comprising at least one dialkanolamine, at least one polyalkylene glycol alkyl ether, and water for nonselective removal of CO₂, H₂S, COS and other acidic gases from a gaseous
10 stream.

There is still a need in the industry for an improved composition for selective removal of COS from gaseous streams containing COS and CO₂. It has now been surprisingly and unforeseeably found out that the addition of a primary alkanolamine,
15 secondary alkanolamine or piperazine compound to a polyalkylene glycol alkyl ether or 1,3-dimethyl-3,4,5,6-tetrahydro-2(1H)-pyrimidinone (DMPT) results in selective removal of COS from the gaseous streams containing same with minimal removal of CO₂.

Summary of the Invention

One aspect of the present invention concerns a solvent composition for removal of COS from a gas stream containing CO₂ and, optionally, other components such as H₂S, CS₂, mercaptans and the like, said composition comprising
20

a) at least one polyalkylene glycol alkyl ether of the formula
25



wherein R₁ is an alkyl group having from 1 to 6 carbon atoms; R₂ is hydrogen or an
30 alkyl group having from 1 to 4 carbon atoms; Alk is an alkylene group, branched or unbranched, having from 2 to 4 carbon atoms, and n is from 1 to 10; and

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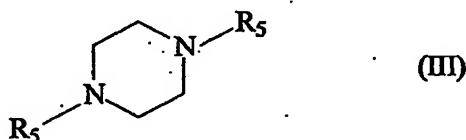
b) at least one alkanolamine compound of the formula



5

or

at least one piperazine compound of formula



10

wherein R_3 is hydrogen, an alkyl group having from 1 to 6 carbon atoms, or the R_4OH group; R_4 is a branched or unbranched alkylene group having from 1 to 6 carbon atoms; R_5 , independently in each occurrence, is hydrogen or an hydroxyalkyl group having from 1 to 4 carbon atoms; and R_6 is hydrogen, an alkyl group having from 1 to 6 carbon atoms or an hydroxyalkyl group having from 1 to 4 carbon atoms.

15

Another aspect the present invention concerns a solvent composition for removal of COS from a gas stream containing CO_2 and, optionally, other components such as H_2S , CS_2 , mercaptans and the like, said composition comprising

20

a) 1,3-dimethyl-3,4,5,6-tetrahydro-2(1H)-pyrimidinone; and

b) at least one alkanolamine compound of the formula

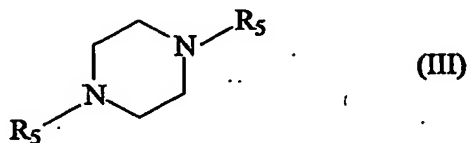
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or

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at least one piperazine compound of formula



wherein R_3 is hydrogen, an alkyl group having from 1 to 6 carbon atoms, or the R_4OH group; R_4 is a branched or unbranched alkylene group having from 1 to 6 carbon atoms; R_5 , independently in each occurrence, is hydrogen or an hydroxyalkyl group having from 1 to 4 carbon atoms; and R_6 is hydrogen, an alkyl group having from 1 to 6 carbon atoms or an hydroxyalkyl group having from 1 to 4 carbon atoms.

In another aspect, the present invention concerns a process for selective removal of COS from a gas stream containing COS and CO_2 , and, optionally, other components said process comprising treating the gas stream with a solvent composition comprising

a) at least one polyalkylene glycol alkyl ether of the formula



wherein R_1 is an alkyl group having from 1 to 6 carbon atoms; R_2 is hydrogen or an alkyl group having from 1 to 4 carbon atoms; Alk is an alkylene group, branched or unbranched, having from 2 to 4 carbon atoms; and n is from 1 to 10; and

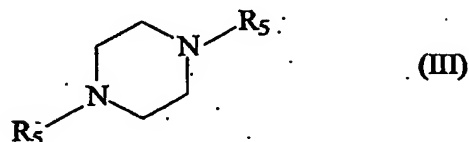
b) at least one alkanolamine compound of the formula



or

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at least one piperazine compound of formula

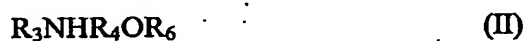


wherein R_3 is hydrogen, an alkyl group having from 1 to 6 carbon atoms, or the R_4OH group; R_4 is a branched or unbranched alkylene group having from 1 to 6 carbon atoms; R_5 , independently in each occurrence, is hydrogen or an hydroxyalkyl group having from 1 to 4 carbon atoms; and R_6 is hydrogen, an alkyl group having from 1 to 6 carbon atoms or an hydroxyalkyl group having from 1 to 4 carbon atoms.

Still in another aspect, the present invention concerns a process for selective removal of COS from a gas stream containing COS and CO_2 , said process comprising treating the gas stream with a solvent composition comprising

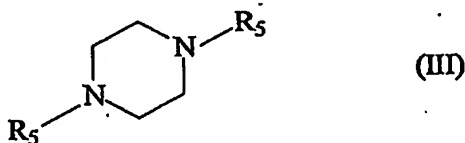
a) 1,3-dimethyl-3,4,5,6-tetrahydro-2(1H)-pyrimidinone; and

b) at least one alkanolamine compound of the formula



or

at least one piperazine compound of formula



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wherein R_3 is hydrogen, an alkyl group having from 1 to 6 carbon atoms, or the R_4OH group; R_4 is a branched or unbranched alkylene group having from 1 to 6 carbon atoms; R_5 , independently in each occurrence, is hydrogen or an hydroxyalkyl group having from 1 to 4 carbon atoms; and R_6 is hydrogen, an alkyl group having from 1 to 6 carbon atoms or an hydroxyalkyl group having from 1 to 4 carbon atoms.

Detailed Description of the Invention

As used herein, the terms "gas", "acid gas", "gaseous stream", and the like, are intended to refer to natural gas, hydrocarbon gas, synthesis gas, steam reformer-type gases, and any other gas containing COS, CO_2 and other gaseous components such as hydrogen sulfide, methane, ethane, propane, hydrogen, carbon monoxide, mercaptans etc. . The expression "minimal additional removal of CO_2 " means removal of CO_2 by the physical solvent plus additive is not substantially larger than removal of CO_2 by the physical solvent alone, all other factors being the same.

In accordance with the present invention, it has been surprisingly discovered that the solvent compositions of the present invention have excellent selectivity for the removal of COS from a gaseous stream containing same with minimal additional removal of CO_2 .

It was completely surprising and unexpected to find out addition of an alkanolamine compound of formula II above or a piperazine compound of formula III above to least one polyalkylene glycol alkyl ether of the formula I above, and in particular to a mixture of polyalkylene glycol ethers of formula I above, such as the SELEXOLTM solvent, removes substantially more of the COS present in the gaseous streams with minimal additional removal of CO_2 .

It was also equally surprising and unexpected to find out that the addition of an alkanolamine compound of formula II above or a piperazine compound of formula III above to 1,3-dimethyl-3,4,5,6-tetrahydro-2(1H)-pyrimidinone removes substantially more of COS present in the gaseous streams with minimal additional removal of CO_2

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Polyalkylene alkyl ethers of formula I suitable in the practice of the present invention are well known and include, without any limitation, diethylene glycol dimethyl ether, diethylene glycol diisopropyl ether, triethylene glycol dimethyl ether, triethylene glycol diisopropyl ether, tetraethylene glycol dimethyl ether, tetraethylene glycol diisopropyl ether, pentaethylene glycol dimethyl ether, pentaethylene glycol diisopropyl ether, hexaethylene glycol dimethyl ether, hexaethylene glycol diisopropyl ether, heptaethylene glycol dimethyl ether, octaethylene glycol dimethyl ether, nonaethylene glycol dimethyl ether, decaethylene glycol dimethyl ether, and any mixture thereof.

Preferred polyethylene glycol alkyl ether is a mixture consisting of a dimethyl ethers of polyethylene glycols of formula $\text{CH}_3\text{O}(\text{C}_2\text{H}_4\text{O})_n\text{CH}_3$ wherein n is from 2 to 10.. Particularly preferred polyethylene glycol alkyl ether is the mixture of dimethyl ethers of polyethylene glycols sold under the trademark SELEXOL by Union Carbide Corporation. SELEXOLTM solvent is a mixture of dimethyl ethers of polyethylene glycols comprising from about 0 to about 0.5 wt% of diethylene glycol dimethyl ether, from about 5 to about 7 wt% of triethylene glycol dimethyl ether, from about 16 to about 18 wt% tetraethylene glycol dimethyl ether, from about 23 to about 25 wt% of pentethylene glycol dimethyl ether, from about 22 to about 24 wt% of hexaethylene glycol dimethyl ether, from about 15 to about 17 wt% of heptaethylene glycol dimethyl ether, from about 8 to about 10 wt% of octaethylene glycol dimethyl ether, from about 3 to about 5 wt% of nonaethylene glycol dimethyl ether, and from about 1 to about 2 wt% of decaethylene glycol dimethyl ether. SELEXOLTM solvent is widely used in gas treating applications for the removal of acidic gases. However, it is known that the removal of COS by the SELEXOLTM solvent is poor due to solvent factors (low solubility) and applications specific factors (low COS partial pressure). Certain amine additives such as bicyclic tertiary amines and tertiary amines have been used, with some success, to improve removal of COS by SELEXOLTM solvent. It has now been discovered that the SELEXOLTM solvent containing alkanolamines of formula II hereinbefore or a piperazine compound of formula III hereinabove is surprisingly selective in removing COS in the presence of CO_2 from gases.

Alkanolamine compounds of formula II useful in the practice of the present invention are well known compounds and include both primary and secondary

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alkanolamines. Preferred alkanolamine compounds of formula II are primary alkanolamines. Non-limiting examples of alkanolamine compounds are monoethanolamine (MEA), diethanolamine (DEA), methylethanolamine (NMEA), diisopropanolamine (DIPA), and diethylene glycolamine (available from Huntsman Corporation under the trademark DGA).

The present invention is particularly useful in the desulfurization portion of an Integrated Combined Cycle Gasification (IGCC) process using an IGCC system consisting of a conventional SELEXOLTM solvent acid gas removal unit, a fixed bed catalytic converter for reducing the gas phase concentration of carbonyl sulfide (COS), and heat exchanger equipment upstream of the SELEXOLTM solvent unit. It has been surprisingly found out that the addition of the alkanolamine compound of formula II above to the SELEXOLTM solvent results in selective removal of COS from the gas feed in the presence of CO₂ with minimal removal of CO₂. The costs associated with the fixed bed catalytic converter are also significantly reduced.

Since the process of the present invention for selective removal of COS from gaseous streams is conducted in the desulfurization portion of an Integrated Combined Cycle Gasification (IGCC) process, the operating conditions of the process are those of the IGCC process. These operating conditions are well known to a person of an ordinary skill in the art.

All parts, percentages and ratios herein are by weight unless otherwise indicated.

The invention will be further clarified by a consideration of the following examples that are intended to be purely exemplary of the present invention and not limiting in any way.

The following components are employed in the examples.

MEA is monoethanolamine;

DEA is diethanolamine;

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TEA is triethanolamine;

NMEA is methylethanoamine;

DIPA is diisopropanolamine;

HEP is hydroxyethylpiperazine;

5 MDEA is methyldiethanolamine;

DMEA is dimethylethanolamine;

DBU is 1,8-diazabicyclo[5.4.0]undec-7-ene;

DBN is 1,5-diazabicyclo[4.3.0]non-5-ene;

10 DABCO is 1,4-diazabicyclo[2.2.2]octane, sold by Air Products and Chemicals, Inc.
under the trademark DABCO;

DMTP is 1,3-dimethyl-3,4,5,6-tetrahydro-2(1H)-pyrimidinone; and

Quinuclidine is 1,4-ethanopiperidine.

Examples

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The performance of SELEXOLTM solvent alone, the mixture of SELEXOLTM solvent, prior art additives, and the solvent of the present invention were evaluated in a bench scale glass absorber-stripper apparatus with the following characteristics:

20

a) standard gas feed conditions (10 mole percent CO₂, 1.6 mole percent COS, and the balance nitrogen, about 3 L/min, 80 °F),

b) standard liquid feed conditions (about 11 cc/min, 80 °F),

c) standard amount of absorber and stripper staging (small trays, 25 absorber, 20 stripper),

25

d) approximately standard amount of stripping heat duty applied,

e) standard amount of the additive used about 3 percent by weight),

f) gas phase analysis by gas chromatography, liquid phase water content by Karl Fisher method,

g) careful attention to ensuring steady state operation,

30

h) liquid phase COS content was not measured, and

i) stripper overhead not sampled for COS or H₂S.

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The results obtained in the performance evaluation of different gas treating solvent are provided in Tables below.

Table 1

Evaluation of Prior Art and Various Additives for Removal of COS by SELEXOLTM solvent ..

| Solvent | COS Absorption (% of feed) | CO ₂ Absorption (% of feed) |
|--|----------------------------|--|
| SELEXOL TM solvent* | 0.7 | 0.7 |
| SELEXOL TM solvent* | 1.2 | 0.2 |
| S+3 wt % 1,4 diazabicyclo[2.2.2]octane (DABCO)* | 2.6 | 0.0 |
| S+3 wt % quinuclidine* | 5.1 | -0.2 |
| S+3 wt % 1,5-diazabicyclo[4.3.0]non-5-ene (DBN)* | 3.1 | -0.6 |
| S+3 wt % 1,8-diazabicyclo[5.4.0]undec-7-ene (DBU)* | 2.5 | 0.5 |
| S+3 wt % triethanolamine (TEA)* | 2.0 | 0.5 |
| S+3 wt % triethanolamine (TEA)* | -0.7 | 2.7 |
| S+3 wt % methyldiethanolamine (MDEA)* | 1.3 | 1.3 |
| S+3 wt % dimethylethanolamine (MDEA)* | 2.0 | 0.0 |
| S+3 wt % hydroxyethylpiperazine (HEP) | 17.1 | 0.7 |
| S+3 wt % diisopropanolamine (DIPA) | 18.9 | 1.0 |
| S+3 wt % diethanolamine (DEA) | 18.9 | 2.8 |
| S+3 wt % diethanolamine (DEA) | 28.3 | 0.1 |
| S+3 wt % monoethanolamine (MEA) | 28.3 | -0.7 |
| S+3 wt % piperazine | 29.1 | 0.8 |
| S+3 wt % methylethanolamine (NMEA) ** | 6.6 | -0.6 |
| S+3 wt % methylethanolamine (NMEA) | 52.1 | 0.9 |
| S+3 wt % methylethanolamine (NMEA) | 50.3 | 1.1 |
| DMTP* | 5.8 | -1.0 |
| DMTP* | 3.6 | -1.1 |
| DMTP +3 wt % diethanolamine | 40.1 | 0.6 |

* not an Example of the present invention

** spurious experimental outcome

10 S = SELEXOLTM solvent

(continued on the next page)

Table 2

| | Comparative Example 1 | Example 1 | Example 2 | Comparative Example 2 | Comparative Example 3 |
|--|--------------------------|---------------------|---------------------|--------------------------|--------------------------|
| Base Solvent | SELEXOL™ Solvent | SELEXOL™ Solvent | SELEXOL™ solvent | DMTP | SELEXOL™ solvent |
| Additive | 0 | Piperazine | NMEA | none | DBU |
| Additive Concentration (wt %) | 25 | 3 | 3 | 0 | 3 |
| # Absorber Trays | 20 | 25 | 25 | 25 | 25 |
| # Stripper Trays | | 20 | 20 | 20 | 20 |
| Total Gas Feed Rate (cc/min) | 2997 | 2996 | 2995 | 3026 | 3008 |
| Feed CO ₂ (mole %) | 10.09 | 10.18 | 10.06 | 9.64 | 11.06 |
| Feed COS (mole %) | 1.48 | 1.51 | 1.51 | 1.21 | 1.63 |
| Sweet CO ₂ (mole %) | 10.02 | 10.1 | 10.12 | 9.74 | 11.01 |
| Sweet COS (mole %) | 1.47 | 1.07 | 1.41 | 1.14 | 1.59 |
| Absorber: | | | | | |
| Lean H ₂ O content (wt %) | 3.2 | 4 | 4.6 | 7.4 | 4.3 |
| Lean Solvent Flow (cc/min) | 11 | 11 | 11 | 11 | 11 |
| Lean T (F) | 80.7 | 78.8 | 79.8 | 79.8 | 80.5 |
| Feed Gas T (F) | 80.8 | 79.1 | 79.5 | 79.3 | 80.3 |
| Sweet Gas T (F) | 81.6 | 79.5 | 80.6 | 79.8 | 80.8 |
| Rich T (F) | 79.3 | 77.6 | 78.1 | 77.9 | 77.1 |
| Absorber P (in H ₂ O) | 28 | 28 | 28 | 28 | 28 |
| Stripper: | | | | | |
| Hot Rich Inlet T (F) | 239.1 | 220.3 | 232.5 | 229.1 | 231.5 |
| Overhead Vap T (C) | 103 | 100 | 103 | 100 | 100 |
| Reboiler T (F) | 264.7 | 258.3 | 254.6 | 270.5 | 259.5 |
| COS Absorption (% of feed) | 0.7 | 29.1 | 6.6 | 5.8 | 2.5 |
| CO ₂ Absorption (% of feed) | 0.7 | 0.8 | -0.6 | -1.0 | 0.5 |

(continued on the next page)

Table 3

| | Comparative Example 4 | Comparative Example 5 | Example 3 |
|--|--------------------------|--------------------------|---------------------|
| Base Solvent | SELEXOL™ Solvent | SELEXOL™ Solvent | SELEXOL™ solvent |
| Additive | DBN | DABCO | DEA |
| Additive Concentration (wt %) | 3 | 3 | 3 |
| Number of Absorber Trays | 25 | 25 | 25 |
| Number of Stripper Trays | 20 | 20 | 20 |
| Total Gas Feed Rate (cc/min) | 3000 | 2999 | 3004 |
| Feed CO ₂ (mole %) | 10.9 | 10.26 | 10.3 |
| Feed COS (mole %) | 1.6 | 1.51 | 1.48 |
| Sweet CO ₂ (mole %) | 10.97 | 10.26 | 10.01 |
| Sweet COS (mole %) | 1.55 | 1.47 | 1.2 |
| Absorber: | | | |
| Lean H ₂ O content (wt %) | 4 | 3.6 | 4.1 |
| Lean Solvent Flow (cc/min) | 11 | 11 | 11 |
| Lean T (F) | 80.7 | 82.3 | 81.1 |
| Feed Gas T (F) | 80.3 | 81.8 | 81 |
| Sweet Gas T (F) | 80.8 | 82.3 | 81.6 |
| Rich T (F) | 79.4 | 79.5 | 79.8 |
| Absorber P (in H ₂ O) | 28 | 28 | 28 |
| Stripper: | | | |
| Hot Rich Inlet T (F) | 227.6 | 246.5 | 226.7 |
| Overhead Vap T (C) | 100 | 102 | 102 |
| Reboiler T (F) | 259.9 | 260.6 | 259.1 |
| COS Absorption (% of feed) | 3.1 | 2.6 | 18.9 |
| CO ₂ Absorption (% of feed) | -0.6 | 0.0 | 2.8 |

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(continued on the next page)

Table 4

| | Example 4 | Comparative Example 6 | Comparative Example 7 | Example 5 | Example 6 |
|--|---------------------|--------------------------|--------------------------|---------------------|---------------------|
| Base Solvent | SELEXOL™ Solvent | SELEXOL™ solvent | SELEXOL™ solvent | SELEXOL™ solvent | SELEXOL™ solvent |
| Additive | MEA | Quinuclidine | none | DEA | NMEA |
| Additive Concentration (wt %) | 3 | 3 | 0 | 3 | .3 |
| Number of Absorber Trays | 25 | 25 | 25 | 25 | 25 |
| Number of Stripper Trays | 20 | 20 | 20 | 20 | 20 |
| Total Gas Feed Rate (cc/min) | 2999 | 2978 | 2985 | 2990 | 3012 |
| Feed CO ₂ (mole %) | 10.09 | 10.06 | 10.13 | 10.03 | 10.11 |
| Feed COS (mole %) | 1.8 | 1.76 | 1.72 | 1.7 | 1.67 |
| Sweet CO ₂ (mole %) | 10.16 | 10.08 | 10.11 | 10.02 | 10.02 |
| Sweet COS (mole %) | 1.29 | 1.67 | 1.7 | 1.43 | 0.8 |
| Absorber: | | | | | |
| Lean H ₂ O content (wt %) | 5.4 | 4.5 | 3.7 | 3.6 | 4 |
| Lean Solvent Flow (cc/min) | 11 | 11 | 11 | 11 | 11 |
| Lean T (F) | 79.7 | 80.7 | 82 | 83.2 | 80.9 |
| Feed Gas T (F) | 80.6 | 79.9 | 80.5 | 81.8 | 83.2 |
| Sweet Gas T (F) | 81.1 | 81 | 81.4 | 83 | 83.5 |
| Rich T (F) | 78.6 | 76.7 | 77.8 | 80.9 | 82.5 |
| Absorber P (in H ₂ O) | 28 | 28 | 28 | 28 | 28 |
| Stripper: | | | | | |
| Hot Rich Inlet T (F) | 222.1 | 213.8 | 209.7 | 207.6 | 201.2 |
| Overhead Vap T (C) | 109 | 103 | 105 | 101 | 100 |
| Reboiler T (F) | 246.6 | 250.2 | 257.5 | 256.9 | 255.1 |
| COS Absorption (% of feed) | 28.3 | 5.1 | 1.2 | 15.9 | 52.1 |
| CO ₂ Absorption (% of feed) | -0.7 | -0.2 | 0.2 | 0.1 | -0.9 |

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(continued on the next page)

Table 5

| | Example 7 | Example 8 | Comparative Example 89 | Example 98 | Comparative Example 9 |
|--|---------------------|---------------------|---------------------------|---------------------|--------------------------|
| Base Solvent | SELEXOL™ Solvent | SELEXOL™ Solvent | DMTP | SELEXOL™ Solvent | SELEXOL™ solvent |
| Additive | NMEA | DIPA | none | HEP | TEA |
| Additive Concentration (wt %) | 3 | 3 | 0 | 3 | 3 |
| Number of Absorber Trays | 25 | 25 | 25 | 25 | 25 |
| Number of Stripper Trays | 20 | 20 | 20 | 20 | 20 |
| Total Gas Feed Rate (cc/min) | 3023 | 3013 | 3004 | 2990 | 3000 |
| Feed CO ₂ (mole %) | 10.08 | 10.08 | 10.02 | 10.06 | 10.01 |
| Feed COS (mole %) | 1.61 | 1.64 | 1.67 | 1.58 | 1.52 |
| Sweet CO ₂ (mole %) | 9.97 | 9.98 | 10.13 | 9.99 | 9.96 |
| Sweet COS (mole %) | 0.8 | 1.33 | 1.61 | 1.31 | 1.49 |
| Absorber: | | | | | |
| Lean H ₂ O content (wt %) | 3.7 | 4 | 8.2 | 3.2 | 3.6 |
| Lean Solvent Flow (cc/min) | 11 | 11 | 11 | 11 | 11 |
| Lean T (F) | 79.4 | 82.9 | 82.4 | 84.2 | 81 |
| Feed Gas T (F) | 78.4 | 81.3 | 81.1 | 82.4 | 79.3 |
| Sweet Gas T (F) | 79.4 | 82.6 | 82 | 83.7 | 80.3 |
| Rich T (F) | 78.3 | 80.1 | 79.6 | 80.2 | 77.5 |
| Absorber P (in H ₂ O) | 28 | 28 | 28 | 28 | 28 |
| Stripper: | | | | | |
| Hot Rich Inlet T (F) | 200.2 | 206.7 | 198.9 | 197.5 | 180.5 |
| Overhead Vap T (C) | 101 | 100 | 104 | 100 | 101 |
| Reboiler T (F) | 255.6 | 255.6 | 271.3 | 258.4 | 255.7 |
| COS Absorption (% of feed) | 50.3 | 18.9 | 3.6 | 17.1 | 2.0 |
| CO ₂ Absorption (% of feed) | 1.1 | 1.0 | -1.1 | 0.7 | 0.5 |

(continued on the next page)

Table 6

| | Comparative Example 10 | Comparative Example 11 | Example 10 | Comparative Example 12 |
|--|---------------------------|---------------------------|------------|---------------------------|
| Base Solvent | SELEXOL™ Solvent | SELEXOL™ Solvent | DMTP | SELEXOL™ solvent |
| Additive | TEA | MDEA | DEA | DMEA |
| Additive Concentration (wt %) | 3 | 3 | 3 | 3 |
| Number of Absorber Trays | 25 | 25 | 25 | 25 |
| Number of Stripper Trays | 20 | 20 | 20 | 20 |
| Total Gas Feed Rate (cc/min) | 3005 | 2995 | 2981 | 2994 |
| Feed CO ₂ (mole %) | 10.17 | 10.01 | 10.09 | 9.95 |
| Feed COS (mole %) | 1.48 | 1.52 | 1.52 | 1.47 |
| Sweet CO ₂ (mole %) | 9.9 | 9.88 | 10.03 | 9.95 |
| Sweet COS (mole %) | 1.49 | 1.5 | 0.91 | 1.44 |
| Absorber: | | | | |
| Lean H ₂ O content (wt %) | 4.2 | 3.8 | 8.6 | 4 |
| Lean Solvent Flow (cc/min) | 11 | 11 | 11 | 11 |
| Lean T (F) | 82.6 | 82.6 | 80 | 80.3 |
| Feed Gas T (F) | 80.4 | 80.4 | 79 | 79.7 |
| Sweet Gas T (F) | 81.9 | 81.8 | 79.6 | 81 |
| Rich T (F) | 77.8 | 78.5 | 79.4 | 76.9 |
| Absorber P (in H ₂ O) | 28 | 28 | 28 | 28 |
| Stripper: | | | | |
| Hot Rich Inlet T (F) | 185.2 | 189.5 | 182.2 | 198.3 |
| Overhead Vap T (C) | 102 | 108 | 105 | 108 |
| Reboiler T (F) | 256.6 | 257.6 | 264.3 | 253.7 |
| COS Absorption (% of feed) | -0.7 | 1.3 | 40.1 | 2.0 |
| CO ₂ Absorption (% of feed) | 2.7 | 1.3 | 0.6 | 0.0 |

As can be seen from the Tables 1-6 hereinabove, certain amine additives of the prior art improve removal of COS without substantially increasing the removal of CO₂. For example, the addition of DABCO, quinuclidine, DBN and DBU to the SELEXOLTM solvent increases the COS removal of to the SELEXOLTM solvent from about 1 % to about 2-5 %.

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As can also be seen from the Tables 1-6 hereinabove, all the solvent compositions of the present invention showed a marked improvement in COS removal with little or no additional CO₂ removal. Overall, the solvent compositions of the present invention the SELEXOLTM solvent and the alkanolamine of formula II or piparazine compound of formula III removed COS in an amount of from about 17 % to about 52 % as compared to the SELEXOLTM solvent alone which removed COS in an amount of only about 1 %. Similarly, the solvent composition of the present invention comprising DMTP and the alkanolamine of formula II removed COS in an amount of about 40 % as compared to DMTP alone which removed COS in an amount of from about 3-6 %. Such magnitude of improved removal of COS by the solvent compositions of the present invention is completely unexpected and unpredictable.

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Other embodiments of the invention will be apparent to those skilled in the art from a consideration of this specification or practice of the invention disclosed herein. It is intended that the specification and examples be considered as exemplary only, with the true scope and spirit of the invention being indicated by the following claims.

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WHAT IS CLAIMED IS:

1. A solvent composition for selective removal of COS from a gas stream containing same, said composition comprising

- a) at least one polyalkylene glycol alkyl ether of the formula



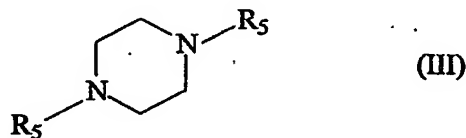
wherein R_1 is an alkyl group having from 1 to 6 carbon atoms; R_2 is hydrogen or an alkyl group having from 1 to 4 carbon atoms; Alk is an alkylene group, branched or unbranched, having from 2 to 4 carbon atoms, and n is from 1 to 10; and

- b) at least one alkanolamine compound of the formula



or

- at least one piperazine compound of formula



wherein R_3 is hydrogen, an alkyl group having from 1 to 6 carbon atoms, or the R_4OH group; R_4 is a branched or unbranched alkylene group having from 1 to 6 carbon atoms; R_5 , independently in each occurrence, is hydrogen or an hydroxyalkyl group having from 1 to 4 carbon atoms; and R_6 is hydrogen, an alkyl group having from 1 to 6 carbon atoms or an hydroxyalkyl group having from 1 to 4 carbon atoms.

2. The solvent composition according to Claim 1 wherein the polyalkylene glycol alkyl ether of the formula I is a mixture of polyalkylene glycol alkyl ethers comprising dimethyl ethers of polyethylene glycols of formula $CH_3O(C_2H_4O)_nCH_3$ wherein n is from 1 to 10.

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3. The solvent composition according to Claim 2 wherein the mixture of polyalkylene glycol alkyl ethers comprises from about 0 to about 0.5 wt% of diethylene glycol dimethyl ether, from about 5 to about 7 wt% of triethylene glycol dimethyl ether, from about 16 to about 18 wt% tetraethylene glycol dimethyl ether, from about 23 to about 25 wt% of pentethylene glycol dimethyl ether, from about 22 to about 24 wt% of hexaethylene glycol dimethyl ether, from about 15 to about 17 wt% of heptaethylene glycol dimethyl ether, from about 8 to about 10 wt% of octaethylene glycol dimethyl ether, from about 3 to about 5 wt% of nonaethylene glycol dimethyl ether, and from about 1 to about 2 wt% of decaethylene glycol dimethyl ether.
4. The solvent composition according to any one of Claims 1 to 3 wherein the component b) is an alkanolamine of formula II in which substituent R_3 is hydrogen.
5. The solvent composition according to any one of Claims 1 to 3 wherein the component b) is monoethanolamine.
6. The solvent composition according to any one of Claims 1 to 3 wherein the component b) is an alkanolamine of formula II in which substituent R_3 is an alkyl group having from 1 to 6 carbon atoms or the R_4OH group.
7. The solvent composition according to Claims 6 wherein the alkanolamine of formula II is selected from the group consisting of diethanolamine, methylethanolamine and diisopropanolamine.
8. The solvent composition according to any one of Claims 1 to 3 wherein the component b) is piperazine.
9. The solvent composition according to any one of Claims 1 to 3 wherein the component b) is hydroxyethylpiperazine.
10. A process for selective removal of COS from a gas stream containing COS and CO_2 , said process comprising contacting the gas stream with a solvent composition comprising
 - a) at least one polyalkylene glycol alkyl ether of the formula



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wherein R_1 is an alkyl group having from 1 to 6 carbon atoms; R_2 is hydrogen or an alkyl group having from 1 to 4 carbon atoms; Alk is an alkylene group, branched or unbranched, having from 2 to 4 carbon atoms; and n is from 1 to 10; and

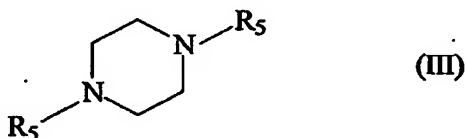
- 5 b) at least one alkanolamine compound of the formula



or

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at least one piperazine compound of formula



- 15 wherein R_3 is hydrogen, an alkyl group having from 1 to 6 carbon atoms, or the R_4OH group; R_4 is a branched or unbranched alkylene group having from 1 to 6 carbon atoms; R_5 , independently in each occurrence, is hydrogen or an hydroxyalkyl group having from 1 to 4 carbon atoms; and R_6 is hydrogen, an alkyl group having from 1 to 6 carbon atoms or an hydroxyalkyl group having from 1 to 4 carbon atoms.

- 20 11. The process according to Claim 10 for selective removal of COS from a gas stream comprising contacting the gas stream with the solvent composition as claimed in Claim 2.
12. The process according to Claim 10 for selective removal of COS from a gas stream comprising contacting the gas stream with the solvent composition as claimed in Claim 3.
- 25 12. The process according to Claim 108 for selective removal of COS from a gas stream comprising contacting the gas stream with the solvent composition as claimed in Claim 4.
13. The process according to Claim 108 for selective removal of COS from a gas stream comprising contacting the gas stream with the solvent composition as claimed in Claim 5.
- 30 14. The process according to Claim 10 for selective removal of COS from a gas stream comprising contacting the gas stream with the solvent composition as claimed in Claim 6.

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15. The process according to Claim 10 for selective removal of COS from a gas stream comprising contacting the gas stream with the solvent composition as claimed in Claim 7.

5 16. The process according to Claim 10 for selective removal of COS from a gas stream comprising contacting the gas stream with the solvent composition as claimed in Claim 8.

17. The process according to Claim 10 for selective removal of COS from a gas stream comprising contacting the gas stream with the solvent composition as claimed in Claim 9.

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18. A solvent composition for selective removal of COS from a gas stream containing same, said composition comprising

b) a) 1,3-dimethyl-3,4,5,6-tetrahydro-2(1H)-pyrimidinone; and

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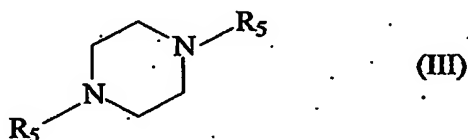
b) at least one alkanolamine compound of the formula



20

or

at least one piperazine compound of formula



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wherein R_3 is hydrogen, an alkyl group having from 1 to 6 carbon atoms, or the R_4OH group; R_4 is a branched or unbranched alkylene group having from 1 to 6 carbon atoms; R_5 , independently in each occurrence, is hydrogen or an hydroxyalkyl group having from 1 to 4 carbon atoms; and R_6 is hydrogen, an alkyl group having from 1 to 6 carbon atoms or an hydroxyalkyl group having from 1 to 4 carbon atoms.

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19. A process for selective removal of COS from a gas stream containing COS and CO_2 , said process comprising contacting the gas stream with a solvent composition comprising

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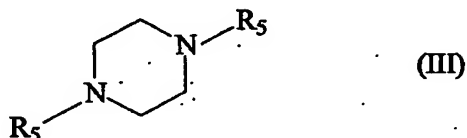
a) 1,3-dimethyl-3,4,5,6-tetrahydro-2(1H)-pyrimidinone; and

b) at least one alkanolamine compound of the formula



or

at least one piperazine compound of formula



wherein R_3 is hydrogen, an alkyl group having from 1 to 6 carbon atoms, or the R_4OH group; R_4 is a branched or unbranched alkylene group having from 1 to 6 carbon atoms; R_5 , independently in each occurrence, is hydrogen or an hydroxyalkyl group having from 1 to 4 carbon atoms; and R_6 is hydrogen, an alkyl group having from 1 to 6 carbon atoms or an hydroxyalkyl group having from 1 to 4 carbon atoms.

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ABSTRACT

Novel solvent composition for selective removal of COS from a gas stream containing same; said composition comprising

- a) at least one polyalkylene glycol alkyl ether of the formula



or

1,3-dimethyl-3,4,5,6-tetrahydro-2(1H)-pyrimidinone

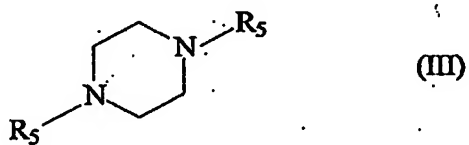
wherein R_1 is an alkyl group having from 1 to 6 carbon atoms; R_2 is hydrogen or an alkyl group having from 1 to 4 carbon atoms; Alk is an alkylene group, branched or unbranched, having from 2 to 4 carbon atoms, and n is from 1 to 10; and

- b) at least one alkanolamine compound of the formula



or

at least one piperazine compound of formula



wherein R_3 is hydrogen, an alkyl group having from 1 to 6 carbon atoms, or the R_4OH group; R_4 is a branched or unbranched alkylene group having from 1 to 6 carbon atoms; R_5 , independently in each occurrence, is hydrogen or an hydroxyalkyl group having from 1 to 4 carbon atoms; and R_6 is hydrogen, an alkyl group having from 1 to 6 carbon atoms or an hydroxyalkyl group having from 1 to 4 carbon atoms.

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